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Dated: December 24, 2003 Signature

(Lawrence E. Russ)

Docket No.: EMCORE 3.0-081

(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Guo et al.

Application No.: 10/721,488

Group Art Unit: N/A

Filed: November 25, 2003

Examiner: Not Yet Assigned

For: GALLIUM NITRIDE-BASED DEVICES AND

MANUFACTURING PROCESS

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

It is respectfully requested that the references listed on the enclosed form be made of record and considered with respect to the above-referenced U.S. patent application. A copy of each non-U.S. patent reference is enclosed. Submission of the present Information Disclosure Statement should not be taken as an admission that the cited references are legally available prior art or that the same are pertinent or material.

In the event that any fee is due in connection with the present Information Disclosure Statement, the Commissioner is hereby authorized to charge the same to our Deposit Account No. 12-1095.

Dated: December 24, 2003

Respectfully submitted,

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Complete if Known			
Application Number	10/721,488		
Filing Date	November 25, 2003		
First Named Inventor	Shiping Guo		
Art Unit	N/A		
Examiner Name	Not Yet Assigned		
Attorney Docket Number	EMCORE 3.0-081		

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Examiner Initials*	Cite No.1	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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Initials* No.1		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)	Date MM-DD-YYYY	Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear	T ⁶
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	NON PATENT LITERATURE DOCUMENTS		
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
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